

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property  
Organization  
International Bureau



(43) International Publication Date  
8 January 2004 (08.01.2004)

PCT

(10) International Publication Number  
WO 2004/003625 A1

(51) International Patent Classification<sup>7</sup>: G02B 26/10,  
A61B 18/20, A61F 9/008, B23K 26/02

(74) Agent: WRAY & ASSOCIATES; Level 4, The Quadrant,  
1 William Street, Perth, Western Australia 6000 (AU).

(21) International Application Number:  
PCT/AU2003/000814

(81) Designated States (*national*): AE, AG, AL, AM, AT, AU,  
AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU,  
CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,  
GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC,  
LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW,  
MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC,  
SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA,  
UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

(22) International Filing Date: 27 June 2003 (27.06.2003)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:  
PS 3261 28 June 2002 (28.06.2002) AU

(84) Designated States (*regional*): ARIPO patent (GH, GM,  
KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW),  
Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM),  
European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE,  
ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO,  
SE, SI, SK, TR), OAPI patent (BF, BJ, CF, CG, CI, CM,  
GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

(71) Applicant (*for all designated States except US*): CLVR  
PTY LTD [AU/AU]; Unit 4, 17 Gibberd Road, Balcatta,  
Western Australia 6021 (AU).

(72) Inventor; and

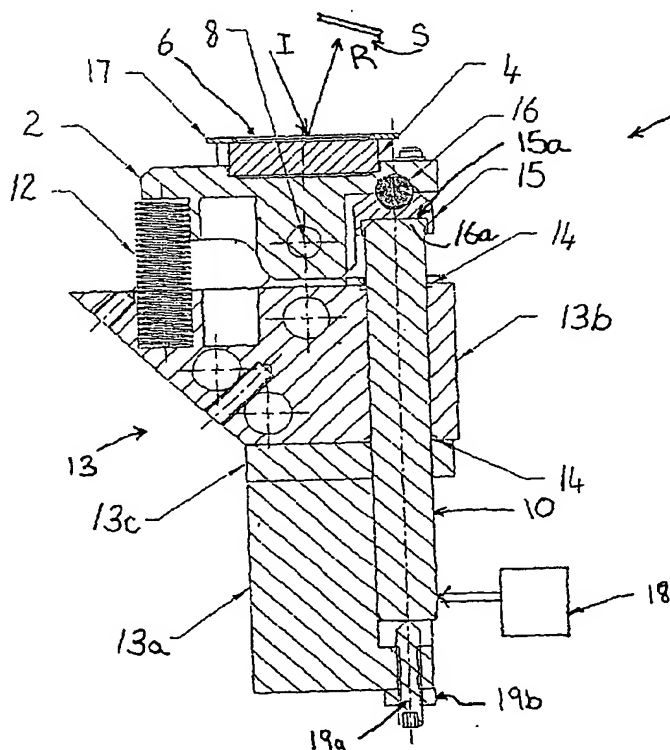
(75) Inventor/Applicant (*for US only*): VAN SAARLOOS,  
Paul, Phillip [AU/AU]; 31 Donar Streey, Innaloo, West-  
ern Australia 6018 (AU).

Published:

— with international search report

[Continued on next page]

(54) Title: SCANNING DEVICE AND METHOD OF SCANNING AN OPTICAL BEAM OVER A SURFACE



(57) Abstract: An optical scanning device (1) to scan an optical beam over a surface (S). The optical scanning device (1) uses a piezoelectric actuator (10) acting on a platform (2) that carries a mirror (4) to pivot the platform (2) about a pivot (8). Voltage is applied to the piezoelectric actuator (10) to pivot the platform (2) about the pivot (8). Changes in the applied voltage result in the angle at which the beam is reflected by the mirror (4) being altered. In this way, the reflected beam (R) can be scanned to different locations on the surface (S). Providing two such optical scanning devices (1a, 1b) or using two piezoelectric actuators (10aa, 10bb) acting on a single platform (2) enables two dimensional scanning of the surface (S) by the optical scanning device/s (1, 1a, 1b). The optical scanning device (1) of the present invention may be used in refractive eye surgery laser apparatus.

**WO 2004/003625 A1**



---

*For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.*

**Title**

Scanning Device and Method of Scanning an Optical Beam Over a Surface

**Field of the Invention**

The present invention relates to an optical scanning device, a laser apparatus  
5 incorporating such an optical scanning device and a method of scanning an  
optical beam over a surface to perform material processing of the surface.

The applications of the present invention include, for example, surgical and  
medical applications, such as operations for correcting refractive errors of the eye  
by photorefractive keratectomy (PRK) or laser in-situ keratomileusis (LASIK). The  
10 present invention also has industrial applications for material processing. Material  
processing examples of industrial applications of the present invention include  
photolithography in microchip manufacture and glass marking.

**Background of the Invention**

The specification refers to and describes content of US patents 5,520,679,  
15 6,339,278, 6,339,470 and 6,342,751. However, neither the disclosures in those  
US patents nor the description contained herein of content of those US patents is  
to be taken as forming part of the common general knowledge solely by virtue of  
the inclusion herein of the reference to and description of content of those US  
patents. Furthermore, this specification describes aspects of prior art optical  
20 scanning systems. However, neither such aspects of prior art optical scanning  
systems nor the description contained herein of such aspects of prior art optical  
scanning systems is to be taken as forming part of the common general  
knowledge solely by virtue of the inclusion herein of reference to and description  
of such aspects of prior art optical scanning systems.

25 A wide range of lasers are suitable for the above applications, including: excimer  
lasers, Nd:YAG, Nd:YLF, Er:YAG, Nd:KGW, Carbon Monoxide, and Carbon  
Dioxide lasers. The wavelengths produced by these lasers range from deep in  
the ultra-violet (UV) to long infra-red (IR) wavelengths.

A feature that is often common among the use of these lasers for material  
30 processing is the need to move the laser beam relative to the material surface

being processed. When the material is not deliberately being moved and the laser beam is being directed to carry out the processing, the movement of the laser beam is often performed by galvanometer or motor driven mirrors and lenses.

- 5 In the field of treating refractive errors by laser ablation, J. T. Lin (US patent 5,520,679) proposed using galvanometer scanners to control a low energy laser beam into an overlapping pattern of adjacent pulses to produce the desired change in the corneal surface. US patent 5,520,679 states that this allows a smaller, lower cost laser to be used for this procedure. US patent 5,520,679 also  
10 states other advantages, including a reduced need for a homogenous beam and better flexibility in design of the treatment.

Galvanometer scanning excimer lasers are currently one of the most common means for correcting refractive errors using the LASIK surgical procedure.

- Although galvanometer scanners have been very successful in scanning lasers  
15 for reshaping corneal tissue and a large range of other applications, they do have some disadvantages. They have a trade-off between the size and weight of the mirror being tilted and the speed by which the galvanometer can adjust its position. Sometimes this results in mirrors that are not large enough for the optical system or using mirrors that are too thin to maintain their required flatness  
20 during the scanning process. Galvanometer scanners also have limited accuracy when the desired scan angle is small (less than 3 degrees).

- The galvanometer scanners used in refractive lasers generally work well at the pulse repetition rates currently used, i.e. 200Hz or below. However, this assumes that the eye is not moving. Tracking the eye has now become an  
25 important part of producing good results for refractive surgery. Between each pulse the position of the eye is measured and then the scanner position adjusted to compensate for any eye movements before the eye moves again. This means that the scanner must be capable of moving much faster than when the laser was operating without an eye tracker. These faster response requirements from the  
30 scanner go beyond the response capabilities of galvanometers. This becomes even more of a problem when the demands of customised surgery require smaller spot sizes to ablate with higher precision and subsequently much higher pulse

repetition rates. Galvanometric scanners would not have adequate response for such a laser system.

5 A problem that sometimes occurs in galvanometric scanners if the eye moves slightly up and down, getting closer or further away from the laser, is that each pulse may not hit the eye in the correct position. Because of the scan angle, if the eye is too close to the laser system then the pulses over-lap more than intended and the total area exposed to the laser is less than intended. If the eye is too far from the laser the opposite occurs. In either case, the result of the surgery is degraded.

10 An alternative drive mechanism to a galvanometer drive mechanism is a piezoelectric drive.

Piezoelectric drives have the advantages of having potentially infinite precision and are capable of generating extremely high forces, so could drive a large mirror very fast. However, piezoelectric drives also have a number of significant  
15 disadvantages, and although they have been used to scan laser beams, they have not been generally accepted for this type of application because of these disadvantages.

The main disadvantage of piezoelectric drive systems is their very limited range of movement. They are therefore not considered to be a potential means of  
20 scanning in applications currently performed by galvanometer scanners. One method that has been used to amplify the range of piezoelectric scanning is to have the piezoelectric crystals push or pull on the end of a metal plate. The metal plate bends and deflects a mirror further than the same piezo would move the mirror if applied behind the edge of the mirror. A device based on this technique  
25 is described by Takeuchi et al in US patent 6,342,751. However, this type of technique creates a non-linear beam deflection and loses much of the potential accuracy of a piezoelectric drive mechanism, and still has a much smaller range of scanning than galvanometer scanners. These types of techniques also suffer from reduced response time, stiffness and have a significantly smaller force/load  
30 capability.

The second significant problem with piezoelectric drive systems, or actuators, is that they have significant hysteresis. This is normally in the order of 10% to 15%

of the range of the movement. This hysteresis is another key reason why piezoelectric driven scanners are currently not used in applications requiring fast complex scan patterns, such as laser systems for refractive surgery. This hysteresis can be corrected by operating the piezoelectric system in a closed loop fashion. This requires a sensor to measure the movement of the system and then a controller that adjusts the voltage to the piezoelectric actuator so that it moves to the desired position. The problem with this is that it significantly reduces the response of the system, and its accuracy is reduced to the accuracy of the sensor. In an application in which tolerances are critical, such as refractive surgery, the hysteresis induced error can be so large that the piezoelectric signal and position sensor signal cannot be compared to check the system is operating correctly. So to achieve a redundant check of scanning performance a second position sensor would need to be used.

Papademetriou, et al in US patent 6,339,470 describes means for scanning lasers across optical fibres. This US patent also describes use of a piezoelectric stack to adjust the angle of a mirror. However, this description complains of the lack of range of such a scanning mechanism as special effort is required to scan the laser across the entrance of a single optical fibre. The main scanning mechanism used in the device described in this US patent relies on acousto-optic deflection of the laser beam, where that scan range must cover more than one optic fibre (which is smaller than the range across an eye). Acousto-optic scanners are relatively complex, have high optical losses and are not suitable for many of the wavelengths used for material processing applications.

The background description in US patent 6,339,278 (Shinohara, et al) describes conventional inclination optical scanners and lists galvanometers, stepper motors and other mechanisms as examples but not piezoelectric mechanisms. However, the invention described in this US patent does use a piezoelectric device, but it is used as a mechanical oscillator to drive an ultrasonic motor that deflects the laser beam.

### 30 Disclosure of the Invention

In accordance with a first aspect of the present invention, there is provided an optical scanning device comprising:

a platform,

a mirror provided on said platform to reflect an optical beam incident on said mirror,

a pivot about which said platform is able to pivot,

5 at least first piezoelectric actuator means to act on said platform to pivot said platform about said pivot in a first direction,

at least first resilient means to bias said platform about said pivot in a second direction opposed to said first direction,

10 wherein said first piezoelectric actuator means acts on said platform at a location in proximity to said pivot, to pivot said platform such that the angle at which said beam is reflected by said mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a first plane over a surface.

In an alternative form, the optical scanning device further comprises:

15 second piezoelectric actuator means to pivot said platform about said pivot in a third direction,

second resilient means to bias said platform about said pivot in a fourth direction opposed to said third direction, and

20 wherein said second piezoelectric actuator means acts on said platform at a location in proximity to said pivot, to pivot said platform such that the angle at which said beam is reflected by said mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a second plane over the surface, such that said reflected beam is scannable over said surface in two dimensions.

25 In accordance with a second aspect of the present invention there is provided an optical scanning apparatus comprising:

a first optical scanning device, and

a second optical scanning device,

said first optical scanning device comprising:

a first platform

a first mirror provided on said first platform to reflect an optical beam incident on said first mirror,

5 a first pivot about which said first platform is able to pivot,

first piezoelectric actuator means to act on said first platform to pivot said first platform about said first pivot in a first direction, and

first resilient means to bias said first platform about said first pivot in a second direction opposed to said first direction, and

10 said second optical scanning device comprising

a second platform

a second mirror provided on said second platform to reflect the optical beam incident on said second mirror,

a second pivot about which said second platform is able to pivot,

15 second piezoelectric actuator means to act on said second platform to pivot said second platform about said second pivot in a third direction, and

second resilient means to bias said second platform about said second pivot in a fourth direction opposed to said third direction,

wherein said first piezoelectric actuator means acts on said first platform at a  
20 location in proximity to said first pivot to pivot said first platform such that the angle at which said beam is reflected by said first mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a first plane, and said second optical scanning device is arranged such that said second mirror receives said beam reflected by said first mirror and said second piezoelectric actuator  
25 means acts on said second platform at a location in proximity to said second pivot to pivot said second platform such that the angle at which said beam is reflected by said second mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a second plane, such that said reflected beam



is scannable over said surface in two dimensions.

In accordance with a third aspect of the present invention there is provided a laser apparatus comprising:

a laser to emit an optical beam,

5 a first optical scanning device, and

a second optical scanning device,

said first optical scanning device comprising

a first platform

10 a first mirror provided on said first platform to reflect an optical beam  
incident on said first mirror,

a first pivot about which said first platform is able to pivot,

first piezoelectric actuator means to act on said first platform to pivot said  
first platform about said first pivot in a first direction, and

15 first resilient means to bias said first platform about said first pivot in a  
second direction opposed to said first direction, and

said second optical scanning device comprising

a second platform

a second mirror provided on said second platform to reflect the optical  
beam incident on said second mirror,

20 a second pivot about which said second platform is able to pivot,

second piezoelectric actuator means to act on said second platform to pivot  
said second platform about said second pivot in a third direction, and

second resilient means to bias said second platform about said second  
pivot in a fourth direction opposed to said third direction,

25 wherein said first piezoelectric actuator means acts on said first platform at a

location in proximity to said first pivot to pivot said first platform such that the angle at which said beam is reflected by said first mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a first plane, and said second optical scanning device is arranged such that said second mirror receives  
5 said beam reflected by said first mirror and said second piezoelectric actuator means acts on said second platform at a location in proximity to said second pivot to pivot said second platform such that the angle at which said beam is reflected by said second mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a second plane, such that said reflected beam  
10 is scannable over said surface in two dimensions to thereby scan the reflected beam over a surface to perform material processing of said surface by the reflected beam and the optical path of the reflected beam from said second optical scanning device to the said surface is substantially one metre or more in length.

Preferably, a third mirror is provided to reflect the reflected beam reflected by said  
15 mirror of said second optical scanning device prior to said reflected beam being reflected to said surface.

More preferably, a fourth mirror is provided to receive the reflected beam from said third mirror and said fourth mirror reflects said reflected beam to said surface.

In accordance with a fourth aspect of the present invention there is provided a  
20 laser apparatus comprising:

a laser to emit an optical beam, and

an optical scanning device comprising

a platform,

a mirror provided on said platform to reflect a said optical beam incident on  
25 said mirror,

a pivot about which said platform is able to pivot,

first piezoelectric actuator means to act on said platform to pivot said platform about said pivot in a first direction,

first resilient means to bias said platform about said pivot in a second

direction opposed to said first direction,

second piezoelectric actuator means to act on said platform to pivot said platform about said pivot in a third direction,

5 second resilient means to bias said platform about said pivot in a fourth direction opposed to said third direction,

wherein said first piezoelectric actuator means acts on said platform at a location in proximity to said pivot, to pivot said platform such that the angle at which said beam is reflected by said mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a first plane and said second piezoelectric  
10 actuator means acts on said platform at a location in proximity to said pivot, to pivot said platform such that angle at which said beam is reflected by said mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a second plane, said first plane and said second plane being substantially mutually orthogonal, to thereby scan the reflected beam over a  
15 surface to perform material processing of said surface by the reflected beam and the optical path of the reflected beam from said optical scanning device to said surface is substantially one metre or more in length.

Preferably, a second mirror is provided to reflect the reflected beam reflected by said mirror of said optical scanning device prior to said reflected beam being  
20 reflected to said surface.

More preferably, a third mirror is provided to receive the reflected beam from said second mirror and said third mirror reflects said beam to said surface.

Preferably, the first plane and the second plane are substantially mutually orthogonal.

25 Preferably, said first piezoelectric actuator means acts on said platform to push said platform and said first resilient means is compressively or expandably resilient.

Alternatively, said first piezoelectric actuator means acts on said platform to pull said platform and said first resilient means is compressively or expandably  
30 resilient.

Preferably, said second piezoelectric actuator means acts on said platform to push said platform and said second resilient means is compressively or expandably resilient.

Alternatively, said second piezoelectric actuator means acts on said platform to pull said platform and said second resilient means is compressively or expandably resilient.

The optical beam may be a laser beam.

The laser apparatus may be a refractive eye surgery laser apparatus, in which case the surface on which the material processing is performed by the reflected beam is the eye of a patient on which the refractive surgery is performed by the reflected beam.

However, the laser apparatus may also be used in other medical applications, in which case the surface on which the material processing is performed by the reflected beam is (human or animal) tissue. Another use of the laser apparatus is as an industrial laser.

In accordance with a fifth aspect of the present invention there is provided a method of scanning an optical beam, in at least a first plane, over a surface using at least one optical scanning device as hereinbefore described comprising

determining a required location for an optical beam to be incident on said surface,  
determining whether a positive or negative change to the voltage applied to a said piezoelectric actuator means is required to pivot said platform to a required position corresponding to the said required location,

comparing the existing position of said platform and the voltage applied to said piezoelectric actuator means with the required position of said platform,

calculating the required voltage to be applied to said piezoelectric actuator means corresponding to the required position of said platform,

applying the said required voltage to said piezoelectric actuator means to move the platform to said required position such that the optical beam is incident on said surface at the said required location.

Preferably, said required position of said platform and the corresponding required voltage to be applied to said piezoelectric actuator means are recorded for use in determining the voltage to be applied to said piezoelectric actuator means for the next location at which said optical beam is to be incident on said surface

- 5 In one preferred embodiment of the method of scanning an optical beam, an optical scanning device in accordance with the alternative form of the optical scanning device in accordance with the first aspect of the present invention is provided to scan the optical beam in two planes over said surface, wherein the steps of the method as hereinbefore described are carried out on each of the first  
10 piezoelectric actuator means and the second piezoelectric actuator means to pivot said platform to the required position for the optical beam to be incident on said surface at said required location.

- In an alternative preferred embodiment of the method of scanning an optical beam, an optical scanning apparatus in accordance with the second aspect of the  
15 present invention is provided to scan the optical beam in two planes over the surface, wherein the steps of the method hereinbefore described in accordance with the fifth aspect of the present invention are carried out on the first piezoelectric actuator means of the first optical scanning device and the second piezoelectric actuator means of the second optical scanning device to pivot the  
20 respective platform of said first optical scanning device and said second optical scanning device to the required position, respectively, for the optical beam to be incident on said surface at the required location.

- The method hereinbefore described may be used in applications such as performing refractive eye surgery on a patient, in which case the surface over  
25 which the optical beam is scanned is the eye of the patient.

The method may also be used in other medical applications, in which case the surface over which the optical beam is scanned is (human or animal) tissue.

The method may also be used in material processing applications in industry.

#### **Brief Description of the Drawings**

- 30 The present invention will now be described, by way of example, with reference to the accompanying drawings, in which:

Figure 1a is a plan view of a first embodiment of an optical scanning device in accordance with an aspect of the present invention;

Figure 1b is a cross section view taken along the line A – A in Figure 1a;

Figure 2 are plots of the relationship between the position of the platform of the scanning device shown in Figure 1 versus the corresponding voltage to be applied to the piezoelectric actuator of the scanning device shown in Figure 1

Figure 3 is a view of an arrangement of two optical scanning devices, of the type shown in Figure 1, arranged so as to scan an optical beam in two dimensions or planes;

Figure 4 is a view of a second embodiment of an optical scanning device in accordance with an aspect of the present invention;

Figure 5 is a schematic illustration of a refractive surgery laser apparatus in accordance with another aspect of the present invention.

#### **Best Mode of Carrying out the Invention**

In Figures 1a and 1b, there is shown an optical scanning device 1 that is able to reflect an incident optical beam I so that the reflected optical beam R can be directed to a surface S such that the reflected optical beam R is scanned over the surface S.

The optical scanning device 1 comprises a platform 2, a mirror 4 having a reflective surface 6, a pivot 8 about which the platform 2 is able to pivot, a piezoelectric stack actuator 10 to pivot the platform 2 about the pivot 8 in a first direction, and a resilient spring 12 to bias the platform 2 about the pivot 8 in a second direction that is opposed to the first direction. The pivot 8 is a pivot shaft.

The optical scanning device 1 is further provided with a body 13 to support the other components of the optical scanning device 1. The body 13 comprises an anchor block 13a and a main block 13b that are separated by a spacer 13c. The main block 13b supports the piezoelectric stack actuator 10. A pair of O rings 14 are provided around the piezoelectric stack actuator 10 at the locations where the piezoelectric stack actuator 10 extends out of the main block 13b. A cap 15 of low

friction material, such as, for example, Teflon, is provided at the end of the piezoelectric stack actuator 10 that is adjacent the platform 2. The cap 15 and the underside of the platform 2 are provided with recesses which accommodate a ball bearing 16. The piezoelectric stack actuator 10 thus acts on the underside of the platform 2 via the cap 15 and the ball bearing 16. The cap 15 is provided with a recess 15a which receives and covers the end 16a of the piezoelectric stack actuator 10. The cap 15 prevents sideways movement of the piezoelectric stack actuator 10 when it acts on the platform 2. A retainer 17 is provided around the mirror 4 to retain the mirror 4 in place.

- 10 A push-pull amplifier 18 is provided to drive the piezoelectric stack actuator 10. An adjustment screw 19 and locking nut 19b are provided to adjust the mid position of the scan range of the optical scanning device 1.

Voltage can be applied to the piezoelectric stack actuator 10 to expand the piezoelectric stack actuator 10. The piezoelectric stack actuator 10 acts on the platform 2 at a location in proximity to the pivot 8. For example, the piezoelectric stack actuator 10 may act on the platform 2 at a location that is spaced substantially 5 to 15mm from the pivot 8. Expansion of the piezoelectric stack actuator 10 pushes on the platform 2 to cause the platform 2 to pivot about the pivot 8 in the direction shown by arrow A in Figure 1. The spring 12 acts to bias the platform 2 about the pivot 8 in a second direction, shown by arrow B in Figure 1, that is opposed to the first direction (shown by arrow A). Thus, when a voltage is applied to the piezoelectric stack actuator 10, the piezoelectric stack actuator 10 acts against the spring 12 to pivot the platform 2 in the direction shown by arrow A. Once the applied voltage is removed from the piezoelectric stack actuator 10, the spring 12 returns the platform 2 to its original position. If the applied voltage is reduced, rather than removed completely, the spring 12 biases the platform 2 in the second direction, shown by arrow B in Figure 1, by an amount corresponding to the reduction in the applied voltage. If the applied voltage to the piezoelectric stack actuator 10 is increased, the piezoelectric stack actuator 10 further expands to cause the platform 2 to pivot about pivot 8 by a further amount corresponding to the increase in the applied voltage.

The spring 12 may be arranged, as required, to bias the platform 2 in a direction opposed to the direction in which the platform 2 is pivoted by the piezoelectric

stack actuator 10. The spring 12 may be compressively or expandibly resilient, as required to provide the biasing action to the platform 2 in a direction opposed to the direction in which the piezoelectric actuator 10 acts on the platform 2.

5 The optical scanning device 1 is able to scan the reflected optical beam R in a first dimension or plane.

The embodiment of the optical scanning device 1 hereinbefore described and illustrated in Figures 1a and 1b is arranged such that the piezoelectric stack actuator 10 acts on the platform 2 to push against the platform 2. However, alternatively the scanning device 1 may be arranged such that the piezoelectric stack actuator 10 acts on the platform 2 to pull the platform 2. In such an arrangement, the ball bearing 16 would be fixed to the platform 2 and the cap 15, which would also be fixed to the end 16a of the piezoelectric stack actuator 10. In that way, when a voltage is applied to the piezoelectric stack actuator 10, it would pull the platform 2 in the direction shown by arrow B in Figure 1. Correspondingly, 15 the spring 12, in such an arrangement, would act to bias the platform 2 about the pivot 8 in the direction shown by arrow A in Figure 1.

For given scan patterns of an optical beam, such as a laser beam, over a surface S, a relationship exists between the voltage applied to the piezoelectric stack actuator 10 and the pivot position of the platform 2, and mirror 4, (also referred to as the "scanning device position" or "scanner position") and consequently the target, or incident, location of the reflected optical beam R on the surface S. 20

The scan patterns have steps between each location that vary in distance and direction in a quasi random fashion. The steps in the scan patterns equate to different incident locations of the beam R on the surface S and correspondingly different scanning device positions. The variation of the steps in the scan pattern in a quasi random fashion is achieved by corresponding quasi random changes in the voltage applied to the piezoelectric stack actuator 10. This is in contrast to a regular scan pattern which uses systematic, i.e. non random changes, in the applied voltage. The reason that a quasi random variation is used is that a different shape is being sculpted each time the scanning device 1 is used and there is a need to move the laser beam across the surface being processed so that consecutive laser beam pulses do not overlap and thermal loading is spread 30



across both the surface and time. There may also be a need to adjust the scan pattern to compensate for movements of the surface being treated that may occur.

For a given voltage applied to the piezoelectric stack actuator 10, the position of the platform 2 may vary by 10% of the full range of movement due to hysteresis occurring in the piezoelectric stack actuator 10, however, the resultant locations are nevertheless reproducible. The positions of the platform 2 corresponding to these locations can also be determined and are reproducible. It is thus possible to determine a relationship between the scan pattern signal, i.e. the voltage applied to the piezoelectric stack actuator 10, and the position of the platform 2 such that the voltage applied to the piezoelectric stack actuator 10 can be adjusted in advance. In this way, the piezoelectric stack actuator 10 can pivot the platform 2, and thereby the mirror 4, into the correct required position so that the beam R is incident on the surface S at the required incident location.

The relationships between the applied voltage and scanning device position can be determined experimentally for given scan patterns and plotted to produce curves representing the relationships. An example of relationships for scanning device position and voltage applied to the piezoelectric stack actuator 10 is shown in Figure 2.

The platform 2 of the scanning device 1 may thus be pivoted to the correct position without the need to rely on closed loop feedback. However, the scanning device 1, when used in a closed loop fashion, would also increase the response speed of the scanning device 1 and allow a position sensor to operate as a redundant check of the position of the scanning device 1.

The scanning device 1 may thus be operated as hereinbelow described.

As stated previously herein, for a given current position of the scanning device 1 and a given current voltage applied to the piezoelectric stack actuator 10, the scanning device 1 will follow a predictable path for changes in the applied voltage to the piezoelectric stack actuator 10. These predictable paths are represented by the curves in Figure 2. The path differs for increases or decreases in the voltage applied to the piezoelectric stack actuator 10 and also depends on the type of piezoelectric device used in the piezoelectric stack actuator 10. These

paths are first determined experimentally for a scanning device 1 employing a piezoelectric stack actuator 10 having a particular piezoelectric device.

When it is required to move the incident location of the beam R on the surface S to a new required location, it is determined whether the new required location  
5 requires a positive or negative change to the voltage applied to the piezoelectric stack actuator 10 to pivot the platform 2 about the pivot point 8 to a new required position, corresponding to the new required location of the beam R, so that the beam R will strike the surface S at the new required location.

The correct path curve is determined that contains the current scanning device  
10 position and applied voltage at the current position of the scanning device. This determination can be made from the relationship between the scanning device position and the applied voltage, which has been previously determined, i.e. as shown in the plot of scanning device position versus applied voltage, as shown in Figure 2.

15 This is then used to calculate the new applied voltage required for the new required position of the scanning device. The current scanning device position and the required applied voltage are then recorded for use in determining the voltage to apply to the piezoelectric stack actuator device 10 for the next required position of the scanning device.

20 If the current position of the scanning device is unknown, e.g. when the scanning device 1 is first switched on, then a voltage of zero can be applied which will produce a fixed position that does not depend on the previous voltage. Effectively, this resets the scanner position to an initial condition.

When a change in the voltage applied to the piezoelectric stack actuator 10  
25 occurs, i.e. a change in the currently applied voltage to the new applied voltage, the voltage changes directly from the currently applied voltage to the new applied voltage, without the applied voltage being returned to zero. However, as an alternative, the voltage may be returned to zero between each change in the applied voltage from the current applied voltage to the new applied voltage.

30 As previously hereinbefore described, the scanning device 1 is able to scan the beam R in a single dimension or plane. In Figure 3 there is shown a scanning

device 1a and scanning device 1b. The scanning devices 1a and 1b are of the same type as the scanning device 1 as previously hereinbefore described with reference to Figures 1a and 1b.

5 The scanning devices 1a and 1b are arranged such that the beam R reflected by the first scanning device 1a can be scanned in a first dimension or plane and is incident upon the mirror 4b of the second optical scanning device 1b. The second optical scanning device 1b is able to reflect the beam R and scan it in a second dimension or plane. The first dimension or plane is substantially orthogonal to the second dimension or plane. In this way, the arrangement of the scanning devices  
10 1a and 1b shown in Figure 3 can scan the reflected beam in two dimensions or planes that are substantially orthogonal to each other. This enables the reflected beam to be scanned in two dimensions over the surface S.

The piezoelectric stack actuator 10b (obscured in Figure. 3) of the second scanning device 1b pivots the platform 2b about the pivot 8b (obscured in Figure  
15 3) of the second scanning device 1b in a direction, or about an axis, that is substantially orthogonal to the direction, or about the axis, that the piezoelectric stack actuator 10a pivots the platform 2a of the first scanning device 1a. Similarly, the spring 12b biases the platform 2b about the pivot 8b of the second scanning device 1b in a direction, or about an axis, that is substantially orthogonal  
20 to the direction, or about the axis, that the spring 12a biases the platform 2a about the pivot 8a of the first scanning device 1a.

In the arrangement shown in Figure 3, the first scanning device 1a receives an incident beam I from a laser 22 and is able to scan the reflected beam R in the plane of the drawing sheet depicting Figure 3. This reflected beam R is incident  
25 upon the mirror 4b of the second scanning device 1b. The beam R is reflected by the mirror 4b of the second scanning device 1b and can be scanned by the second scanning device 1b in a plane that is substantially orthogonal to the plane of the drawing sheet depicting Figure 3, i.e. the beam R is reflected by the mirror 4b, in a plane, out of the drawing sheet depicting Figure 3.

30 The description of the relationship between the voltage applied to the piezoelectric stack actuator 10 and the pivot position of the platform 2 and the previous description herein of the operation of the scanning device 1 with reference to

Figures 1a, 1b and 2 applies to the scanning devices 1a and 1b shown in Figure 3. The scanning devices 1a and 1b operate together to enable the reflected beam R to be scanned in two dimensions or planes.

In Figure 4 there is shown a second embodiment of an optical scanning device 11. The optical scanning device 11 is similar to the optical scanning device 1, except that the optical scanning device 11 is provided with a pair of piezoelectric stack actuators 10aa and 10bb and a pair of resilient springs 12aa and 12bb and the pivot 8ab allows the platform 2 to pivot in at least two directions, or about two axes, that are substantially mutually orthogonal.

- 10 The pivot 8ab may be provided near a corner of the platform 2. The pivot 8ab may be provided as a ball that allows the platform 2 to swivel in any direction.

The piezoelectric stack actuators 10aa and 10bb and the springs 12aa and 12bb may be provided in proximity to the pivot 8ab. The piezoelectric stack actuators 10aa and 10bb may be provided such that they act on the platform 2 in proximity to the pivot 8ab, for example, at a location spaced substantially 5 to 15mm from the pivot 8ab.

The scanning device 11 permits the platform 2 to pivot about two substantially orthogonal dimensions or axes. Thus, the scanning device 11 provides an alternative to using two scanning devices 1a and 1b, as shown in Figure 3, to achieve scanning of the beam R about two substantially orthogonal dimensions or axes to enable the reflected beam to be scanned in two dimensions or planes.

Voltage applied to the piezoelectric stack actuator 10aa causes the piezoelectric stack actuator 10aa to expand. This in turn, causes the platform 2 to pivot about the pivot 8ab in a first direction, shown by arrow C in Figure 4, against the action of the spring 12aa. The spring 12aa acts to bias the platform 2 about the pivot 8ab in a second direction, shown by arrow F in Figure 4, that is opposed to the direction shown by arrow C. Similarly, voltage applied to the piezoelectric stack actuator 10bb causes the piezoelectric stack actuator 10bb to expand. This in turn, causes the platform 2 to pivot about the pivot 8ab in the direction shown by arrow D in Figure 1, against the action of the spring 12bb. The spring 12bb acts to bias the platform 2 about the pivot 8ab in a direction, shown by arrow G in Figure 1, that is opposed to the direction indicated by arrow D. The axes about

which the piezoelectric stack actuators 10aa and 10bb pivot the platform 2 are mutually orthogonal. The piezoelectric stack actuator 10aa and spring 12aa enable a reflected beam R to be scanned in a first dimension or plane and the piezoelectric stack actuator 10bb and spring 12bb enable the reflected beam R to be scanned in a second dimension or plane. The first dimension or plane is substantially orthogonal to the second dimension or plane.

In this way, the reflected beam R can be scanned in two dimensions or planes over a surface S.

The description of the relationship between the voltage applied to the piezoelectric stack actuator 10 and the pivot position of the platform 2 and the operation of the scanning device 1, previously hereinbefore described with reference to Figures 1 and 2, also applies to the operation of the scanning device 11.

In Figure 5 there is shown a refractive eye surgery laser apparatus 20.

The refractive eye surgery laser apparatus 20 comprises an optical scanning unit ("OSU"), a laser 22 and first and second mirrors 24 and 26, respectively.

The OSU may be either an arrangement of two scanning devices 1a and 1b, as shown in Figure 3, or a scanning device 11 as shown in Figure 4. In this way, the OSU is able to reflect an incident beam I so that the reflected beam R can be scanned in two dimensions or planes.

The laser 22 emits the laser beam I which is directed to the mirrors 4aa and 4bb, or mirror 4, of the OSU. The mirrors 4aa and 4bb, or mirror 4, reflects the incident beam I as reflected beam R.

The reflected beam R is reflected by the mirrors 4aa and 4bb, or mirror 4, of the OSU to a mirror 24. The mirror 24, in turn, reflects the beam R to a second mirror 26. The mirror 26 reflects the beam R and directs it to the surface to be treated, in this case being the eye E of a patient P.

The OSU is operated, in the manner hereinbefore described with reference to the scanning device 1 and Figs 1 and 2, to scan the beam R over the surface of the eye E in the required scan pattern to carry out refractive surgery on the eye E using the laser beam R.

The pivotal movement of the platforms 2a and 2b, or the platform 2, of the OSU about the pivots 8a and 8b, or the pivot 8ab, causes the path of the reflected beam R to change with changes in the OSU position. The changes in the path of the reflected beam R are preserved by the mirrors 24 and 26. In this way, the path of the beam R that is reflected from the surface 26 changes. These changes correspond to the changes of the OSU. In this way, the beam R reflected by the mirror 26 can be scanned over the eye E to the required locations where refractive surgery is carried out by the beam R.

To achieve the required scan range for the beam R reflected from the mirror 26 to scan the eye E of a patient P, the optical path between the OSU and the eye E is arranged such that it is substantially one metre or more. That is to say, the distance travelled by the beam R from the OSU to the mirror 24, from the mirror 24 to the mirror 26 and from the mirror 26 to the eye E is substantially one metre or more. It is to be understood that by "substantially one metre or more" it is meant that distances of slightly less than one metre, as well as distances of one metre or more, are suitable. This distance enables the refractive laser surgery apparatus 20, employing the OSU, to scan the range required to perform surgery on the eye E.

The refractive eye surgery laser apparatus 20, hereinbefore described, provides an advantage in processing a material, such as corneal tissue of the eye, that may move or may not be exactly the same distance from the laser system each time that the laser 22 is operated to emit a beam I. In that regard, in the OSU, employing a piezoelectrically driven actuator 10, the scan angle, i.e. the angle through which the beam R passes to scan the eye E from one extremity to the other, is much smaller than in prior art systems. Therefore, vertical movements or misalignments of the eye E during surgery will have a much smaller adverse effect on the surgical result compared to prior art galvanometric scanning systems.

Whilst the scanning device of the present invention has been exemplified by its use in a refractive surgery laser system, it may be used in other laser apparatus in which a material is processed by a laser beam.

Modifications and variations such as would be apparent to a skilled addressee are

deemed to be within the scope of the present invention.

Throughout the specification, unless the context requires otherwise, the word "comprise" or variations such as "comprises" or "comprising", will be understood to imply the inclusion of a stated integer or group of integers but not the exclusion of

5 any other integer or group of integers.

## Claims

1. An optical scanning device characterised in that it comprises:

a platform,

5 a mirror provided on said platform to reflect an optical beam incident on said mirror,

a pivot about which said platform is able to pivot,

at least first piezoelectric actuator means to act on said platform to pivot said platform about said pivot in a first direction,

10 at least first resilient means to bias said platform about said pivot in a second direction opposed to said first direction,

wherein said first piezoelectric actuator means acts on said platform at a location in proximity to said pivot, to pivot said platform such that the angle at which said beam is reflected by said mirror is altered to alter the path of the reflected beam to  
15 thereby scan the reflected beam in a first plane over a surface.

2. An optical scanning device according to claim 1, characterised in that it further comprises

second piezoelectric actuator means to act on said platform to pivot said platform about said pivot in a third direction,

20 second resilient means to bias said platform about said pivot in a fourth direction opposed to said third direction, and

wherein said second piezoelectric actuator means acts on said platform at a location in proximity to said pivot, to pivot said platform such that the angle at which said beam is reflected by said mirror is altered to alter the path of the  
25 reflected beam to thereby scan the reflected beam in a second plane over said surface, such that said reflected beam is scannable over said surface in two dimensions.

3. An optical scanning device characterised in that it comprises:



a platform,

a mirror provided on said platform to reflect an optical beam incident on said mirror,

a pivot about which said platform is able to pivot,

- 5 first piezoelectric actuator means to act on said platform to pivot said platform about said pivot in a first direction,

first resilient means to bias said platform about said pivot in a second direction opposed to said first direction,

- 10 second piezoelectric actuator means to act on said platform to pivot said platform about said pivot in a third direction, and

second resilient means to bias said platform about said pivot in a fourth direction opposed to said third direction,

- 15 wherein said first piezoelectric actuator means acts on said platform at a location in proximity to said pivot, to pivot said platform such that the angle at which said beam is reflected by said mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a first plane over a surface, and said second piezoelectric actuator means acts on said platform at a location in proximity to said pivot, to pivot said platform such that the angle at which said beam is reflected by said mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a second plane over said surface, such that said reflected beam is scannable over said surface in two dimensions.

- 25 4. An optical scanning device according to any one of the preceding claims, characterised in that a cap is provided over an end of said first piezoelectric actuator means that is located proximate said platform to limit sideways movement of said first piezoelectric actuator means proximate said platform.

5. An optical scanning device according to any one of the preceding claims, characterised in that a push-pull amplifier is provided to drive said first piezoelectric actuator means.

6. An optical scanning device according to any one of the preceding claims,

characterised in that said first piezoelectric actuator means acts on said platform to push said platform and said first resilient means is compressively resilient.

7. An optical scanning device according to any one of claims 1 to 5, characterised in that said first piezoelectric actuator means acts on said platform to push said platform and said first resilient means is expandably resilient.

8. An optical scanning device according to any one of claims 1 to 5, characterised in that said first piezoelectric actuator means acts on said platform to pull said platform and said first resilient means is compressively resilient.

9. An optical scanning device according to any one of claims 1 to 5, characterised in that said first piezoelectric actuator means acts on said platform to pull said platform and said first resilient means is expandably resilient.

10. An optical scanning device according to any one of claims 2 to 9, characterised in that a cap is provided over an end of said second piezoelectric actuator means that is located proximate said platform to limit sideways movement of said second piezoelectric actuator means proximate said platform.

11. An optical scanning device according to any one of claims 2 to 9, characterised in that a push-pull amplifier is provided to drive said second piezoelectric actuator means.

12. An optical scanning device according to any one of claims 2 to 9, characterised in that said second piezoelectric actuator means acts on said platform to push said platform and said second resilient means is compressively resilient.

13. An optical scanning device according to any one of claims 2 to 9, characterised in that said second piezoelectric actuator means acts on said platform to push said platform and said second resilient means is expandably resilient.

14. An optical scanning device according to any one of claims 2 to 9, characterised in that said second piezoelectric actuator means acts on said platform to pull said platform and said second resilient means is compressively resilient.

15. An optical scanning device according to any one of claims 2 to 9, characterised in that said second piezoelectric actuator means acts on said platform to pull said platform and said second resilient means is expandably resilient.
- 5 16. An optical scanning device according to any one of the preceding claims, characterised in that said optical beam is a laser beam.
17. An optical scanning device according to any one of claims 2 to 16, characterised in that said first plane and said second plane are substantially mutually orthogonal.
- 10 18. An optical scanning apparatus characterised in that it comprises:
- a first optical scanning device, and
- a second optical scanning device,
- said first optical scanning device comprising
- a first platform
- 15 a first mirror provided on said first platform to reflect an optical beam incident on said first mirror,
- a first pivot about which said first platform is able to pivot,
- first piezoelectric actuator means to act on said first platform to pivot said first platform about said first pivot in a first direction, and
- 20 first resilient means to bias said first platform about said first pivot in a second direction opposed to said first direction, and
- said second optical scanning device comprising
- a second platform
- a second mirror provided on said second platform to reflect the optical
- 25 beam incident on said second mirror,
- a second pivot about which said second platform is able to pivot,

second piezoelectric actuator means to act on said second platform to pivot said second platform about said second pivot in a third direction, and

second resilient means to bias said second platform about said second pivot in a fourth direction opposed to said third direction,

- 5 wherein said first piezoelectric actuator means acts on said first platform at a location in proximity to said first pivot to pivot said first platform such that the angle at which said beam is reflected by said first mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a first plane, and said second optical scanning device is arranged such that said second mirror receives  
10 said beam reflected by said first mirror and said second piezoelectric actuator means acts on said second platform at a location in proximity to said second pivot to pivot said second platform such that the angle at which said beam is reflected by said second mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a second plane, such that said reflected beam  
15 is scannable over said surface in two dimensions.

19. An optical scanning apparatus according to claim 18, characterised in that a cap is provided over an end of said first piezoelectric actuator means that is located proximate said first platform to limit sideways movement of said first piezoelectric actuator means proximate said first platform.

- 20 20. An optical scanning apparatus according to claim 18 or 19, characterised in that a first push-pull amplifier is provided to drive said first piezoelectric actuator means.

21. An optical scanning apparatus according to any one of claims 18 to 20, characterised in that said first piezoelectric actuator means acts on said first  
25 platform to push said first platform and said first resilient means is compressively resilient.

22. An optical scanning apparatus according to any one of claims 18 to 20, characterised in that said first piezoelectric actuator means acts on said first platform to push said first platform and said first resilient means is expandably  
30 resilient.

23. An optical scanning apparatus according to any one of claims 18 to 20,

characterised in that said first piezoelectric actuator means acts on said first platform to pull said first platform and said first resilient means is compressively resilient.

24. An optical scanning apparatus according to any one of claims 18 to 20, characterised in that said first piezoelectric actuator means acts on said first platform to pull said first platform and said first resilient means is expandably resilient.

25. An optical scanning apparatus according to any one of claims 18 to 24, characterised in that a cap is provided over an end of said second piezoelectric actuator means that is located proximate said second platform to limit sideways movement of said second piezoelectric actuator means proximate said second platform.

26. An optical scanning apparatus according to any one of claims 18 to 25, characterised in that a second push-pull amplifier is provided to drive said second piezoelectric actuator means.

27. An optical scanning apparatus according to any one of claims 18 to 26, characterised in that said second piezoelectric actuator means acts on said second platform to push said second platform and said second resilient means is compressively resilient.

28. An optical scanning apparatus according to any one of claims 18 to 26, characterised in that said second piezoelectric actuator means acts on said second platform to push said second platform and said second resilient means is expandably resilient.

29. An optical scanning apparatus according to any one of claims 18 to 26, characterised in that said second piezoelectric actuator means acts on said second platform to pull said second platform and said second resilient means is compressively resilient.

30. An optical scanning apparatus according to any one of claims 18 to 26, characterised in that said second piezoelectric actuator means acts on said second platform to pull said second platform and said second resilient means is expandably resilient.

31. An optical scanning apparatus according to any one of claims 18 to 30, characterised in that said optical beam is a laser beam.

32. An optical scanning apparatus according to any one of claims 18 to 31, characterised in that said first plane and said second plane are substantially  
5 mutually orthogonal.

33. A laser apparatus characterised in that it comprises:

a laser to emit an optical beam, and

an optical scanning device according to any one of claims 1 to 17,

wherein the reflected beam is scannable over the surface to perform material  
10 processing of said surface by the reflected beam and the optical path of the reflected beam from said optical scanning device to said surface is substantially one metre or more in length.

34. A laser apparatus characterised in that it comprises:

a laser to emit an optical beam, and

15 an optical scanning device comprising

a platform,

a mirror provided on said platform to reflect a said optical beam incident on said mirror,

a pivot about which said platform is able to pivot,

20 first piezoelectric actuator means to act on said platform to pivot said platform about said pivot in a first direction,

first resilient means to bias said platform about said pivot in a second direction opposed to said first direction,

25 second piezoelectric actuator means to act on said platform to pivot said platform about said pivot in a third direction,

second resilient means to bias said platform about said pivot in a fourth

direction opposed to said third direction,

wherein said first piezoelectric actuator means acts on said platform at a location in proximity to said pivot, to pivot said platform such that the angle at which said beam is reflected by said mirror is altered to alter the path of the reflected beam to  
5 thereby scan the reflected beam in a first plane and said second piezoelectric actuator means acts on said platform at a location in proximity to said pivot, to pivot said platform such that angle at which said beam is reflected by said mirror is altered to alter the path of the reflected beam to thereby scan the reflected  
10 beam in a second plane, such that said reflected beam is scannable over said surface in two dimensions to thereby scan the reflected beam over the surface to perform material processing of said surface by the reflected beam and the optical path of the reflected beam from said optical scanning device to said surface is substantially one metre or more in length.

35. A laser apparatus according to claim 33 or 34, characterised in that it further  
15 comprises a second mirror to reflect the reflected beam reflected by said mirror of said optical scanning device prior to said reflected beam being reflected to said surface.

36. A laser apparatus according to claim 35, characterised in that it further  
20 comprises a third mirror to receive the reflected beam from said second mirror and said third mirror is arranged to reflect said beam to said surface.

37. A laser apparatus according to any one of claims 33 to 36, characterised in that said laser apparatus is a refractive eye surgery laser apparatus, and the surface on which the material processing is performed by the reflected beam is the eye of a patient on which the refractive surgery is performed by the reflected  
25 beam.

39. A laser apparatus comprising:

a laser to emit an optical beam, and

an optical scanning apparatus according to any one of claims 18 to 32,

wherein the reflected beam is scannable over a surface to perform material  
30 processing of said surface by the reflected beam and the optical path of the

reflected beam from said second optical scanning device to the said surface is substantially one metre or more in length

40. A laser apparatus comprising:

a laser to emit an optical beam,

5 a first optical scanning device, and

a second optical scanning device,

said first optical scanning device comprising

a first platform

10 a first mirror provided on said first platform to reflect an optical beam incident on said first mirror,

a first pivot about which said first platform is able to pivot,

first piezoelectric actuator means to act on said first platform to pivot said first platform about said first pivot in a first direction, and

15 first resilient means to bias said first platform about said first pivot in a second direction opposed to said first direction, and

said second optical scanning device comprising

a second platform

a second mirror provided on said second platform to reflect the optical beam incident on said second mirror,

20 a second pivot about which said second platform is able to pivot,

second piezoelectric actuator means to act on said second platform to pivot said second platform about said second pivot in a third direction, and

second resilient means to bias said second platform about said second pivot in a fourth direction opposed to said third direction,

25 wherein said first piezoelectric actuator means acts on said first platform at a



location in proximity to said first pivot to pivot said first platform such that the angle at which said beam is reflected by said first mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a first plane, and said second optical scanning device is arranged such that said second mirror receives  
5 said beam reflected by said first mirror and said second piezoelectric actuator means acts on said second platform at a location in proximity to said second pivot to pivot said second platform such that the angle at which said beam is reflected by said second mirror is altered to alter the path of the reflected beam to thereby scan the reflected beam in a second plane, such that said reflected beam  
10 is scannable over said surface in two dimensions to thereby scan the reflected beam over a surface to perform material processing of said surface by the reflected beam and the optical path of the reflected beam from said second optical scanning device to the said surface is substantially one metre or more in length.

41. A laser apparatus according to claim 39 or 40, characterised in that a third  
15 mirror is provided to reflect the reflected beam reflected by said second mirror prior to said reflected beam being reflected to said surface.

42. A laser apparatus according to claim 41, characterised in that a fourth mirror is provided to receive the reflected beam from said third mirror and said fourth mirror is arranged to reflect said reflected beam to said surface.

20 43. A method of scanning an optical beam, in at least a first plane, over a surface using an optical scanning device according to any one of claims 1 to 17, characterised in that it comprises

determining a required location for the optical beam to be incident on said surface,  
determining whether a positive or negative change to the voltage applied to a said  
25 piezoelectric actuator means is required to pivot said platform to a required position corresponding to the said required location,

comparing the existing position of said platform and the voltage applied to said piezoelectric actuator means with the required position of said platform,

calculating the required voltage to be applied to said piezoelectric actuator means  
30 corresponding to the required position of said platform,

applying the said required voltage to said piezoelectric actuator means to move said platform to said required position such that the optical beam is incident on said surface at the said required location.

5 44. A method according to claim 43, characterised in that said required position of said platform and the corresponding required voltage to be applied to said piezoelectric actuator means are recorded for use in determining the voltage to be applied to said piezoelectric actuator means for the next location at which said optical beam is to be incident on said surface.

10 45. A method according to claim 43 or 44, characterised in that the steps of the method recited in claim 43 or 44 are carried out on each of the first piezoelectric actuator means and the second piezoelectric actuator means to pivot said platform to the required position for the optical beam to be incident on said surface at said required location, to thereby scan the optical beam in two planes, such that the optical beam is scannable in two dimensions over said surface.

15 46. A method of scanning an optical beam, in two planes, over a surface using an optical scanning apparatus according to any one of claims 18 to 32, characterised in that it comprises

determining a required location for the optical beam to be incident on said surface,  
20 determining whether a positive or negative change to the voltage applied to each of said first piezoelectric actuator means and said second piezoelectric is required to pivot each said platform to a required position corresponding to the said required location,

comparing the existing position of each said platform and the voltage applied to said first piezoelectric actuator means and said second piezoelectric means,  
25 respectively, with the required position of each said platform,

calculating the required voltage to be applied to said first piezoelectric actuator means and said second piezoelectric means, respectively, corresponding to the required position of each respective said platform,

30 applying the said required voltage to said first piezoelectric actuator means and said second piezoelectric actuator means, respectively, to move each said

platform to the respective said required position such that the optical beam is incident at the said required location.

47. A method according to claim 46, characterised in that said required position of each said platform and the corresponding required voltage to be applied to said
- 5 first piezoelectric actuator means and said second piezoelectric actuator means, respectively, are recorded for use in determining the voltage to be applied to said first piezoelectric actuator means and said second piezoelectric actuator means, respectively, for the next location at which said optical beam is to be incident on said surface.



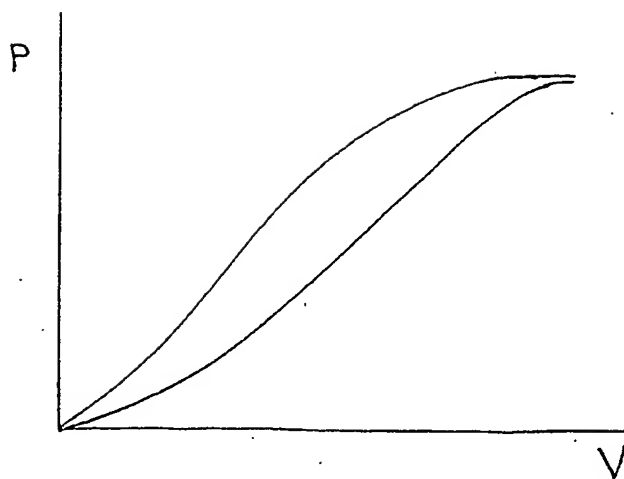


FIGURE 2

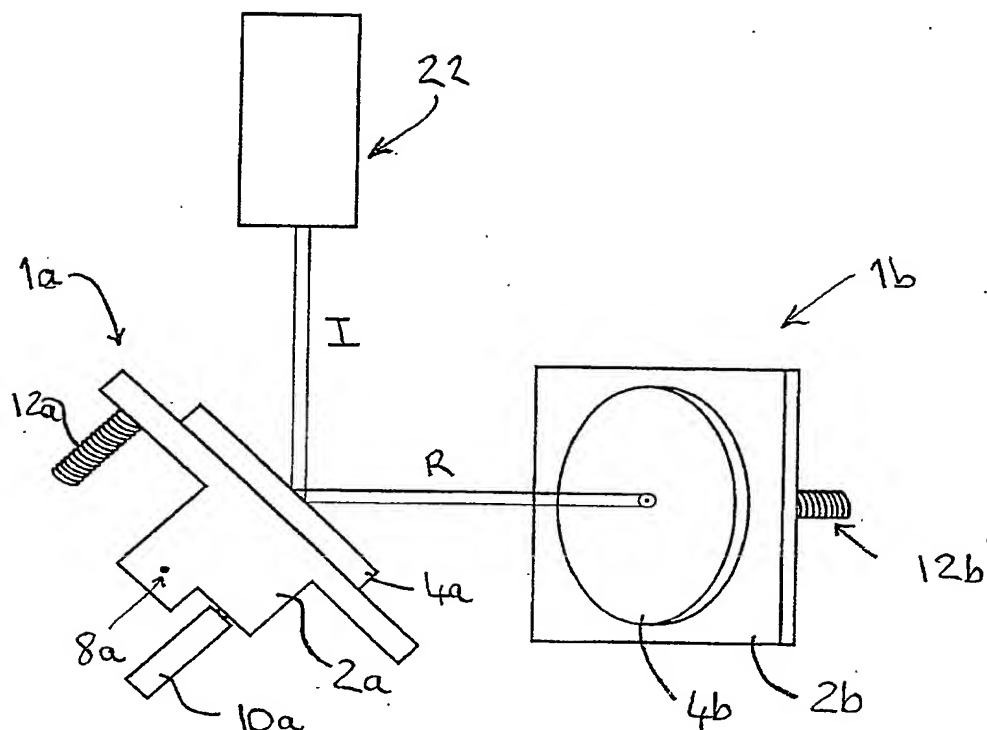


FIGURE 3

10/519382

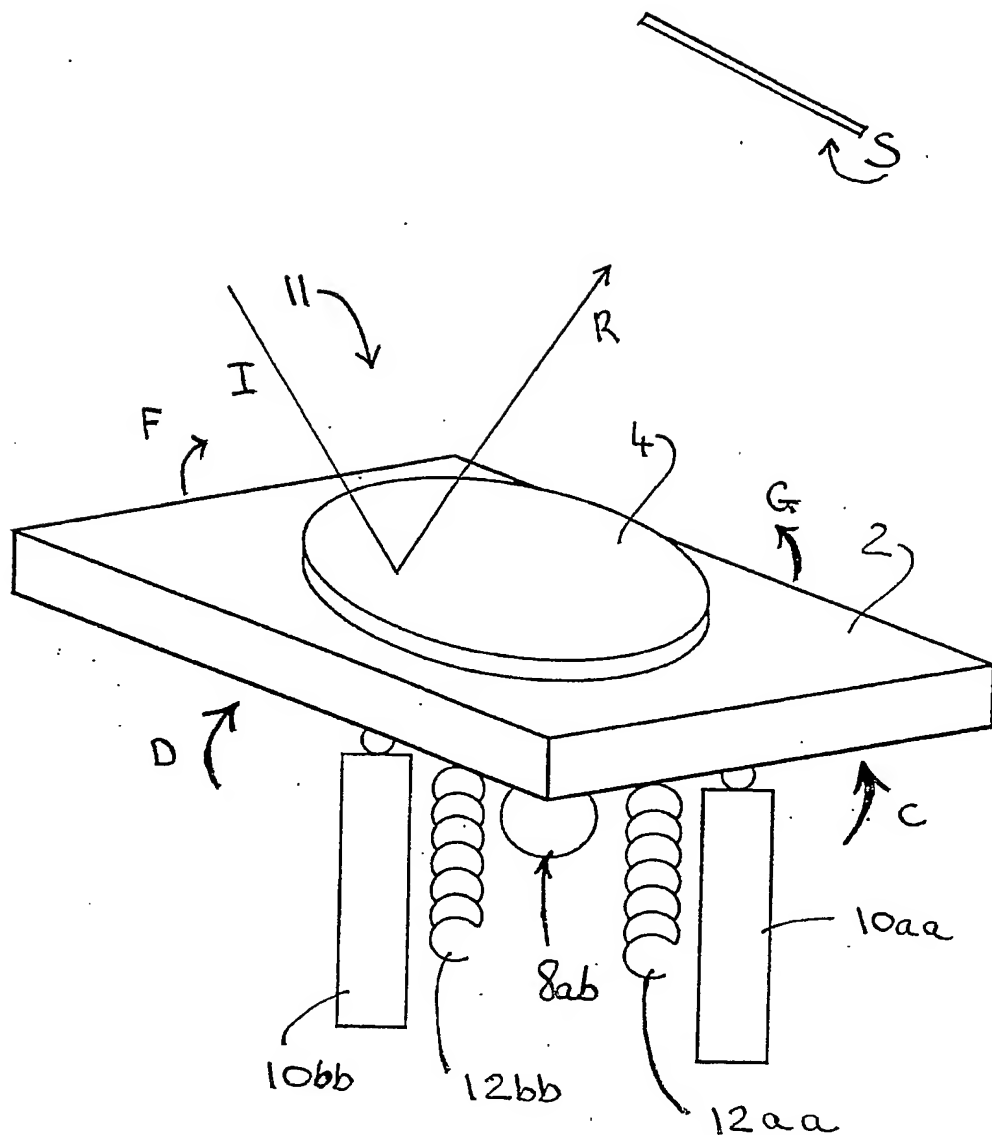


FIGURE 4

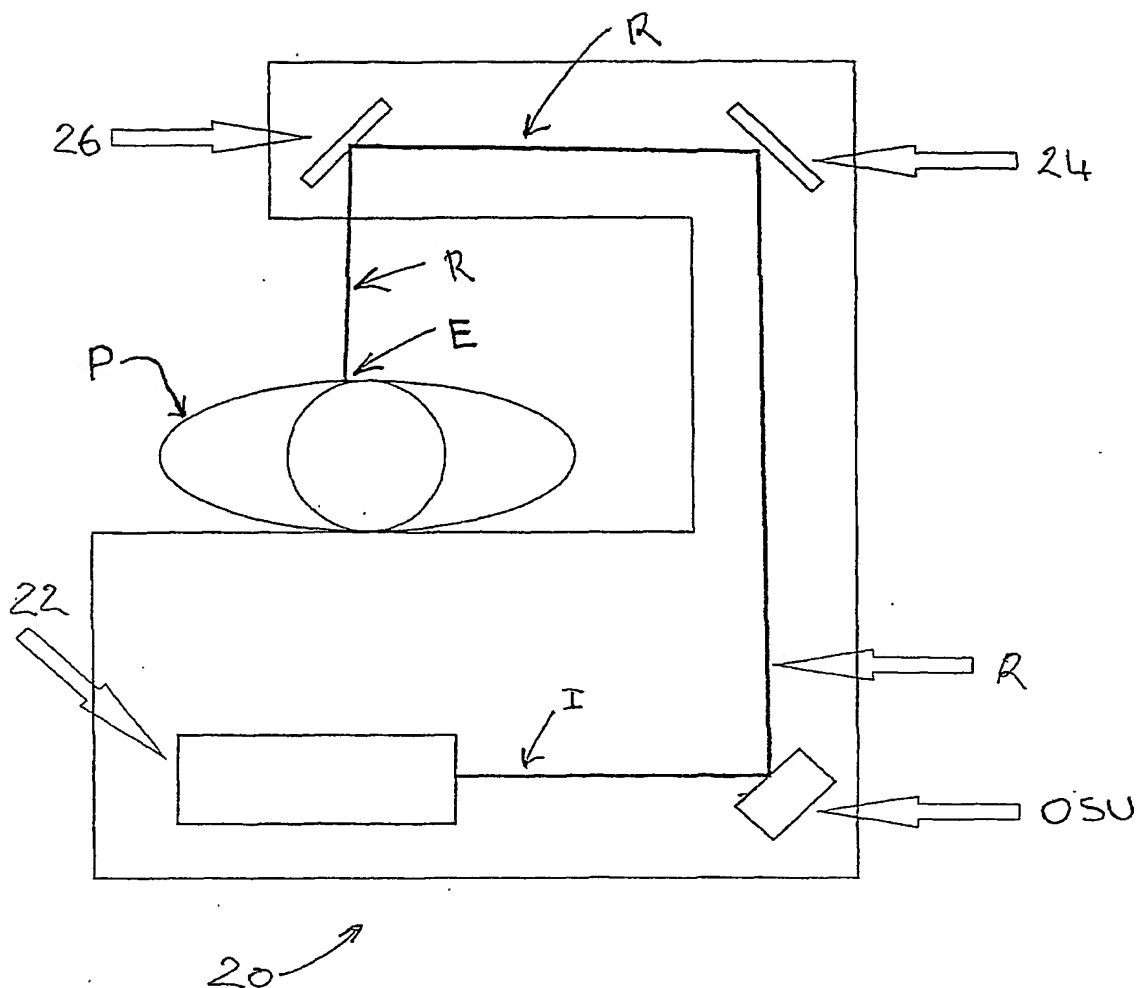


FIGURE 5



# INTERNATIONAL SEARCH REPORT

International application No.

PCT/AU03/00814

<b>A. CLASSIFICATION OF SUBJECT MATTER</b>		
Int. Cl. <sup>7</sup> : G02B 26/10, A61B 18/20, A61F 9/008, B23K 26/02		
According to International Patent Classification (IPC) or to both national classification and IPC		
<b>B. FIELDS SEARCHED</b>		
Minimum documentation searched (classification system followed by classification symbols)		
Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched		
Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)		
DWPI: laser, scan, piezoelectric, mirror, angle, pivot, spring, eye and similar terms		
<b>C. DOCUMENTS CONSIDERED TO BE RELEVANT</b>		
Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X	US 6166841 A (MELVILLE) 26 December 2000 Column 6 line 9-column 8 line 15, figures 8-11	1-3, 5-9, 11-16, 33-37
X	SU 1778738 A (INST TEK KIBERNET AN BRUS) 30 November 1992 Figures	1-3, 5-9, 11-17, 33-37
X	GB 2241592 A (STEVENS et al) 4 September 1991 Page 6 line 11-page 7 line 15, figure 2	1, 5-9, 16, 33, 40-42
<input checked="" type="checkbox"/> Further documents are listed in the continuation of Box C <input checked="" type="checkbox"/> See patent family annex		
<p>* Special categories of cited documents:</p> <p>"A" document defining the general state of the art which is not considered to be of particular relevance</p> <p>"E" earlier application or patent but published on or after the international filing date</p> <p>"L" document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified)</p> <p>"O" document referring to an oral disclosure, use, exhibition or other means</p> <p>"P" document published prior to the international filing date but later than the priority date claimed</p> <p>"T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention</p> <p>"X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone</p> <p>"Y" document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art</p> <p>"&amp;" document member of the same patent family</p>		
Date of the actual completion of the international search 18 July 2003		Date of mailing of the international search report 25 JUL 2003
Name and mailing address of the ISA/AU AUSTRALIAN PATENT OFFICE PO BOX 200, WODEN ACT 2606, AUSTRALIA E-mail address: pct@ipaustalia.gov.au Facsimile No. (02) 6285 3929		Authorized officer  GREG POWELL Telephone No : (02) 6283 2308

**INTERNATIONAL SEARCH REPORT**

International application No.

**PCT/AU03/00814**

<b>C (Continuation). DOCUMENTS CONSIDERED TO BE RELEVANT</b>		
<b>Category*</b>	<b>Citation of document, with indication, where appropriate, of the relevant passages</b>	<b>Relevant to claim No.</b>
<b>X</b>	WO 02/46819 A (SIEMENS AKTIENGESELLSCHAFT) 13 June 2002 Page 3 lines 18-28, page 5 lines 1-19, figures 2, 3	1, 5-9, 16, 33
<b>X</b>	JP 2001-179180 A (VICTOR CO OF JAPAN LTD) 3 July 2001 Figures and paragraphs 2, 15-23 of translation from www1.ipdl.jpo.go.jp/PA1/cgi-bin/PA1INDEX	1, 5-9, 16, 33

# INTERNATIONAL SEARCH REPORT

Information on patent family members

International application No.

PCT/AU03/00814

This Annex lists the known "A" publication level patent family members relating to the patent documents cited in the above-mentioned international search report. The Australian Patent Office is in no way liable for these particulars which are merely given for the purpose of information.

Patent Document Cited in Search Report		Patent Family Member	
US	6166841	US	5995264
SU	1778738	NONE	
GB	2241592	EP	596880
		US	5600478
		WO	93/03456
WO	02/46819	NONE	
JP	2001-179180	NONE	
END OF ANNEX			